

Notic of References Cited				Application No. 09-882289		Applicant(s) Wharner et al.	
				Examiner George Goudreau		Group Art Unit 1763	
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★	DOCUMENT NO.	DATE	NAME			CLASS	SUBCLASS
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* A copy of this reference is not being furnished with this Office action.
(See Manual of Patent Examining Procedure, Section 707.05(a).)